Xuemiao Li

List of Publications by Year
in descending order

Source: https://exaly.com/author-pdf/3394494/publications.pdf

Version: 2024-02-01

10 papers	113 citations	1684188 5 h-index	1720034 7 g-index
10 all docs	10 docs citations	10 times ranked	91 citing authors

#	Article	IF	Citations
1	Synthesis of a Fluoromethacrylate Hydroxystyrene Block Copolymer Capable of Rapidly Forming Sub-5 nm Domains at Low Temperatures. ACS Macro Letters, 2019, 8, 368-373.	4.8	43
2	Fast self-assembly of polystyrene-b-poly(fluoro methacrylate) into sub-5 nm microdomains for nanopatterning applications. Journal of Materials Chemistry C, 2019, 7, 2535-2540.	5.5	31
3	Methacrylic Block Copolymers Containing Liquid Crystalline and Fluorinated Side Chains Capable of Fast Formation of 4 nm Domains. Macromolecules, 2020, 53, 8757-8764.	4.8	11
4	Poly(2-vinylpyridine)-b-poly(fluorinated methacrylate) Block Copolymers Forming 5 nm Domains Containing Metallocene. ACS Applied Polymer Materials, 2020, 2, 3601-3611.	4.4	11
5	Synthesis of Liquid Crystalline Block Copolymers Self-assembled into Sub-5 nm Microdomains. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2019, 32, 413-416.	0.3	8
6	Ultra-Fast Block Copolymers for Sub-5 nm Lithographic Patterning. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2018, 31, 483-486.	0.3	5
7	Synthesis and Directed Self-Assembly of Modified PS-b-PMMA for Sub-10 nm Nanolithography. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2017, 30, 83-86.	0.3	3
8	Fast annealing DSA materials designed for sub-5 nm resolution. , 2018, , .		1
9	Development of 90 NM & 5 NM High Resolution Advanced Lithographic Patterning Materials. , 2020, , .		0
10	Synthesis of Highly Ordered Si-Containing Fluorinated Block Copolymers. Journal of Photopolymer Science and Technology = [Fotoporima Konwakai Shi], 2021, 34, 329-334.	0.3	0